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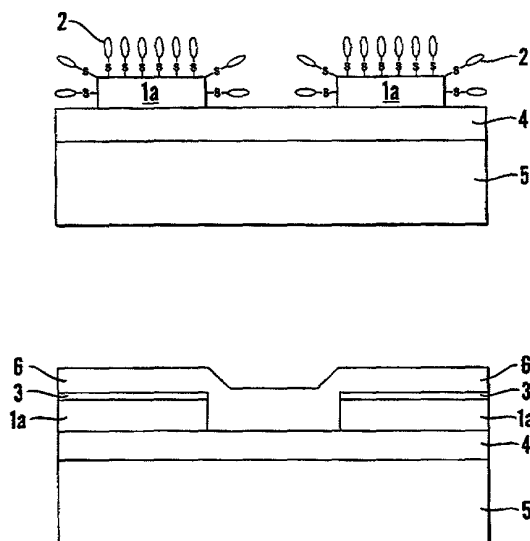
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19993266 30 June 1999 (30.06.1999) NO</p> <p>(71) Applicant (<i>for all designated States except US</i>): THIN FILM ELECTRONICS ASA [NO/NO]; P.O. Box 1872 Vika, N-0124 Oslo (NO).</p> <p>(71) Applicant and</p> <p>(72) Inventor (<i>for all designated States except US</i>): WANG,</p> | <p>Jianna [CN/US]; 5 Dolores Ave., Waltham, MA 02452 (US).</p>
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- (54) Title: A MEANS FOR ELECTRICAL CONTACTING OR ISOLATION OF ORGANIC OR INORGANIC SEMICONDUCTORS AND A METHOD FOR ITS FABRICATION**



(57) Abstract: In a means for electrical contacting or isolation of organic or inorganic semiconductors in electronic and optoelectronic devices, particularly thin-film devices, the means comprises a substrate (1) in the form of a contact material (1a) or an isolating material (4). A charge transfer material (2) is provided patterned or unpatterned on or at the surface of the substrate and includes charge transfer components in the form of donors and/or acceptors. The charge transfer material forms a self-assembling layer (3) on one or more atomic and/or molecular layers. The charge transfer material (2) has a direct or indirect bond to the surface of the substrate (1) and further forms a charge transfer complex with a thereabove adjacently provided organic or inorganic semiconductor (6). The charge transfer material (2) then forms a donor or acceptor material in the charge transfer complex depending upon respectively whether the semiconductor (6) itself is an acceptor or donor material.

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